

WHAT IS CLAIMED IS:

1. An exposure mask for use in step exposure of a pattern to be formed on a TFT substrate, the exposure mask
5 having pattern-forming portions each formed with a pattern portion for one pixel and shield portions each for blocking transmission of exposure light for one pixel,

wherein in an area corresponding to an overlapping exposure area in the step exposure, a plurality of the
10 pattern-forming portions and a plurality of the shield portions are mosaically arranged, such that areas between one shield portions and other shield portions vertically or laterally adjacent to the one shield portions are shielded.

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2. The exposure mask according to claim 1, wherein arrangement of the pattern-forming portions and the shield portions in a one-end portion of the exposure mask is complementary to arrangement of the pattern-forming
20 portions and the shield portions in another-end portion opposite to the one-end portion.

3. The exposure mask according to claim 1, wherein the shield portions comprise a plurality of types of
25 shield portions each corresponding to one pixel and different in size.

4. The exposure mask according to claim 1, wherein the pattern-forming portions and the shield portions are arranged mosaically, in respective units of two or more adjacent pattern-forming portions and two or more adjacent shield portions identical in number to a number of pattern-forming portions of one unit.

5. The exposure mask according to claim 1, wherein the shield portions are arranged such that the shield portions are progressively reduced in number toward a center of the exposure mask.

6. A method of exposing a pattern to be formed on a TFT substrate by step exposure using an exposure mask having pattern-forming portions each formed with a pattern portion for one pixel and a plurality of shield portions each for blocking transmission of exposure light for one pixel,

the method comprising:

a first exposure step of exposing a first pattern using a mask pattern in which a plurality of the pattern-forming portions and a plurality of the shield portions are mosaically arranged at opposite end portions thereof, such that areas between one shield portions and other shield portions vertically or laterally adjacent to the one shield portions are shielded; and

a second exposure step of exposing a second pattern

using the exposure mask, such that an end of the second pattern to be formed in adjacent to the first pattern and an end of the first pattern overlap each other.